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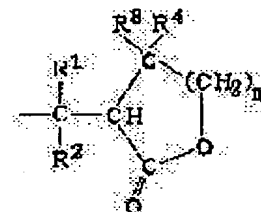
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## (54) RADIATION SENSITIVE RESIN COMPOSITION

## (57)Abstract:

PROBLEM TO BE SOLVED: To provide a radiation sensitive resin composition superior in transparency to radiation and resolution, and also the balance of characteristics including sensitivity and developability, and pattern forms, and dry etching resistance, and the like.

SOLUTION: The radiation sensitive resin composition comprises (A) an alkali-insoluble or hardly soluble resin having, as acid dissociable groups, repeating units each represented by the formula and solubilizable in alkali, when these acid-dissociable groups and/or lactone rings in these groups are dissociated, and (B) a radiation-sensitive acid-generator. In the formula, each of R1-R4 is, independently, an H atom or a 1-6C straight or branched alkyl or 5- to 8-membered cycloalkyl group and R1 and R2, or R3 and R4 may combine with each other to form a 5- to 8-membered cycloalkyl group; and (n) is an integer of 1-4.



## LEGAL STATUS

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